

PHOTOELECTRIC MEASUREMENT METHODS AND THE UNIVERSAL MEASUREMENT SYSTEM FOR PRECISE PARAMETER DETERMINATION OF SEMICONDUCTOR STRUCTURES

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ABSTRACT

In this article a new Multifunctional System for Photoelectric Measurements of Semiconductor Structures (MSPM) is presented. The system enables very accurate photocurrent measurements at levels as low as 10 fA. Measured structures can be biased by sequences of DC voltages and stimulated by light beams of predefined wavelengths and powers. The software controls all the system actions allowing flexibility in retrieving data stored in the related databases.